An ion thrusting system is disclosed comprising an ionization membrane having at least one area through which a gas is passed, and which ionizes the gas molecules passing therethrough to form ions and electrons, and an accelerator element which accelerates the ions to form thrust. In some variations, a potential is applied to the ionization membrane may be reversed to thrust ions in an opposite direction. The ionization membrane may also include an opening with electrodes that are located closer than a mean free path of the gas being ionized. Methods of manufacture and use are also provided.

26 Claims, 4 Drawing Sheets
FIG. 1

Breakdown Voltage (volts)

\[ Pd \text{ (mm-mm Hg)} \]

FIG. 2A

134 133 120 134

132 122 106

130
FIG. 3

FIG. 6

FIG. 7
ION THRUSTING SYSTEM


This invention was made in part with Government support under contract NASA-1407 awarded by NASA. The Government has certain rights in this invention.

BACKGROUND

Many different applications are possible for ionization systems. For example, it is desirable to form a pumpless, low mass sampling system for a mass spectrometer.

Conventional mass spectrometers often use “hard” techniques of producing ion fragments, in which certain parts of the molecule are forcibly removed, to form the fragmented ion. For example, the fragments may be produced by ultraviolet, radioactive, and/or thermal electron ionization techniques. Some of these techniques, and specifically the thermal technique, may require a vacuum to enhance the life of the filament source.

Different systems which use ionization are known. A quadrupole and magnetic sector/time of flight system ionizes a sample to determine its content. These devices, have limitations in both operation and size. Many devices of this type may operate over only a relatively small mass sampling range. These devices may also suffer from efficiency issues, that is the ions might not be efficiently formed.

Many of these systems also require a very high vacuum to avoid ion collisions during passage through the instrument. For example, the systems may require a vacuum of the level of such as 10^-6 Torr. A vacuum pump must be provided to maintain this vacuum. The vacuum pump consumes power, may be heavy, and also requires a relatively leak free environment. This clashes with the usual desire to miniaturize the size of such a device.

Other applications could be desirable for ionization, if an ionization system were sufficiently small. However, the existing ionization systems have problems and difficulties in fabrication which has prevented them from being used in certain applications.

SUMMARY

The present application describes a special ionization membrane, along with applications of this special ionization membrane that are facilitated by the membrane.

A first application uses the ionization membrane as part of a mass spectrometer.

Another application uses the ionization membrane for other applications. According to an aspect of this invention, the electrodes are formed closer than the mean free path of a specified gas, for example the gas being considered. This may ionize gas molecules in free space. Different applications of this soft ionization technique are described including using this system in a mass spectrometer system, such as a rotating field mass spectrometer. This may also be used in a time of flight system.

In an embodiment, a pumpless mass spectrometer is described which does not include a pump for either forming the vacuum or for driving the ions.

Another embodiment describes using this system for an electrochemical system. Another application describes using this system in propulsion.

BRIEF DESCRIPTION OF THE DRAWINGS

These and other aspects will now be described in detail with reference to the accompanying drawings, wherein FIG. 1 shows Paschen curves for various gases; FIGS. 2a–2e show details of the special ionization membrane of the present system, with FIG. 2b showing a cross-section along the line 2b–2b in FIG. 2c; and FIG. 2a showing a close-up detail of one of the holes in FIG. 2b; FIG. 3 shows an ion mobility spectrometer; FIG. 4 shows a solid-state ionization membrane being used in an electrochemical device; and FIG. 6 shows this propulsion system in its housing with top and bottom accelerator grids.

DETAILED DESCRIPTION

Gas may be ionized in a high electric field. Avalanche arcing may be produced by the gas ionization. It has been found by the present inventor, however, that when the “mean free path” between molecules is greater than electrode separation, only ionization occurs.

FIG. 1 shows the Paschen curves for various gases. This represents the breakdown voltage of the gas at various characteristic points. On the left side and under each Paschen curve ionization of the gas occurs using the special membrane described herein. This technique is “soft” in the sense that it ionizes without fragmenting the molecular structure of the gas being ionized. That means that large organic compounds can be analyzed without breaking them into smaller atomic fragments.

Details of the membrane are shown in FIGS. 2A–2C, with FIGS. 2A & 2B showing cross sections of the membrane of FIG. 2C. The miniature ionization device 99 is formed by micromachining an array of small holes 100 through a relatively thin membrane 105. The membrane 105 may be, for example, of sub micron thickness. The material 106 of the substrate itself may be silicon or any other easy-to-machinable material. Metal electrodes 120, 122 are located on respective sides of the membrane 100. The metal can be any material such as chrome or titanium or gold.

In formation of the membrane 99, a plurality of holes such as 130 are formed from the bottom 132. The holes may generally taper as shown towards the top portion 133 of the hole. The top portion 133 of the hole 130 may have a dimension 137 which may be, for example, 2 to 3 microns. Openings may be formed in the top metal coating 120, and in the bottom metal coating 122. For example, the hole may be formed by focused ion-beam milling (maskless process).

The substrate material 106 also includes a dielectric layer 134 which can be for example, silicon nitride, alumina, or any other similar material that has a similar dielectric breakdown. The thickness 136 of the dielectric layer sets the distance between the metal electrodes 120 and 122. The dielectric thickness can be to 200–300 nm. The dielectric can in fact be thinner than 200 nm, in fact can be any thickness, with thicknesses of 50 nm being possible.
In a preferred system, the distance between the electrodes 120, 122 is less than 1 micron. When this small separation is maintained, electric field strengths on the range of mega volts per meter are produced for each volt of potential difference between the electrodes 120, 122.

The inventor has noted that the membranes could not be formed simply from the thin, sub micron elements. Membranes that are formed in this way could be too fragile to sustain a pressure difference across the membrane, or to survive a minor mechanical shock. In this embodiment, the thicker supporting substrate part 105 is used, and is back-etched through to the membrane. By forming the structure in this way, that is with a relatively thick substrate portions such as 105/106, separated by back etched holes such as 100, the structure of the device can be maintained while keeping a relatively small distance between the electrodes.

An embodiment is described herein which uses the field ionizer array, which may be a micromachined field ionizer membrane, with a lateral accelerator, which is coupled to a mass spectrometer. An array of cathodes may be deployed to detect the position of impinging of the particles.

The cathode electrodes may be derived from an active pixel sensor array of the type described in U.S. Pat. No. 5,471,215, and as conventional may include various types of on-chip matrix processing. This system may use an electrode sensor of 1024 by 1024 pixels, with sub pixel centroiding and radial integration. The active pixel sensor itself may have a sensitivity on the order of 10^{-17} amps. By adding pixel current processing, another two orders of magnitude of trajectories, and these detector electrodes may be supplied in opposition to the other field. This fields applied to the filter electrode may straighten the trajectory of specific ion species, allowing their passage through the filter. The other ion species collide with the electrodes. Sweeping of the DC field may facilitate detection of the complete ion spectrum.

Detector electrodes 620 are located downstream of the filter electrodes 615. The selected ions have straightened trajectories, and these detector electrodes 620 deflect the straightened-trajectory ions into detection electrodes, where they are detected. The detected current provides a direct measure of the number of ions. The number of ions is effectively proportional to the vapor concentration.

It should be understood that this gas feed system could be either upstream or downstream in this way.

Another embodiment uses this ionization technique to form a free space ion thruster.

Yet another embodiment describes use of an ionizer of this type in a fuel cell. Previous fuel cell proton exchange membranes have used platinum or other electrooxidation catalysts to facilitate proton transfer. In this system, the oxidation gas or gases 700 is passed through the pores of a membrane 705 under an extreme electric field as shown in FIG. 4. The oxidation gas or gases 700 are completely ionized on passage through the membrane. The gas 708 once ionized, now has a positively charged aspect. The gas 708 drifts to the membrane 710 where the electrooxidized state of the gas enhances its transfer through the cathode. The transfer of atomic species through the membrane in this way reduces the partial pressure between the ionizer 705 and the membrane 710, this causing further inflow through the ionizer pores of the oxidation gas 702. The ionizer potential may alternatively be maintained positive with respect to the cathode membrane in order to accelerate the ions to an increased velocity before imprinting on the cathode membrane which forms the accelerator grid.

Another embodiment, shown in FIG. 5, uses this ionization membrane as part of a miniature ion thruster. This may form a thrust system using propellant gas. Propellant gas 800 is ionized by passing it through the pores of a membrane 805 of the type described above, under a high electric field. This forms positively charged ions 809 from the gas. The ions 809 enter another field 808 between the membrane and a porous accelerator grid 810. This other field 808 accelerates the ions to an increased velocity, and expels them from the thrustor as 820.
The electrons are caused to move back behind the membrane where a small electric field and magnetic field may linearly and rotationally accelerate the electron beam around to eject the electrons from the thruster with the same vector but reduced velocity as the ion beam. Since the ion and electron currents are substantially identical, this system becomes effectively charge neutral.

This system may use a small tube 820 of 1.5 cm long; 2 mm in diameter, of dielectric materials such as quartz. The tube 820 may be eutectically bonded to the top of the membrane 805. The micromachined conductive grid is similarly affixed to the top of the tube. The bottom of the membrane may also be eutectically bonded to a thruster housing 825. That housing may contain another accelerating grid 830 and magnets.

An exterior view of the structure is shown in FIG. 6, which shows the tube for any particular accelerator grid potential, the thrust of the engine is determined by the gas flow through the membrane pores. This system may use a plurality of miniature ionization tubes such as the one described above, that are disbursed across the surface of the structure. These tubes may be deployed individually or collectively by connecting them into a circuit. The ions from each of these tubes are accelerated under the influence of a localized electric field that is along the vector representing the least distance to the peripheral grid. The aggregate thrust is the geometrically integrated mass-momentum of all connected free space ion thrusters.

In this embodiment, a bipolar ion thruster may allow reversing the electrode potentials on the ionization membrane, causing the electrons to pass through the membrane, while ions move behind the membrane. The high velocity ions are expelled from the front of the thruster, and electrons are expelled from the rear of the thruster. This engine can therefore be reversed in this way.

When used in a vacuum, a low-pressure gas may need to be introduced into the membrane aperture that has a velocity sufficient to carry the gas into the ionization field. Gas expands in a vacuum and has its molecules accelerated to supersonic speed while cooling, and directed through the membrane. Once ionized, the accelerating ions will create a partial vacuum behind them, which partial vacuum encourages further gas flow through the membrane. Gas that remains behind the membrane is ionized, and its negative field directs those ions through the membrane.

This system may have many different applications including biomedical applications such as a breath analyzer, as well as applications in other systems. It may have applications environment monitoring, personal monitoring, reviewing of water quality, automobile MAP control, detection of explosives, chemical and biological agent detection, and in an artificial nose type product.

What is claimed is:

1. An apparatus for use with an ion thrusting system, the apparatus comprising: an ionization membrane having at least one area through which a gas is passed, and which ionizes the gas molecules passing therethrough to form ions and electrons; and an accelerator element which accelerates the ions to form thrust, wherein said ionization membrane comprises: an insulating element having at least one opening, a first conductive electrode extending on a first surface of said insulating element at the at least one opening and a second conductive electrode extending on a second surface of the insulating element at the at least one opening, wherein said insulating element separates said first and second conductive electrodes at said at least one opening by a thickness less than the mean free path of the molecules within the gas being ionized.

2. The apparatus of claim 1 wherein the accelerator element is a cathode.

3. The apparatus of claim 1 wherein the ionization membrane has one of said areas.

4. The apparatus of claim 1 wherein the ionization membrane has a plurality of said areas.

5. The apparatus of claim 1 wherein said first and second conductive electrodes are separated by less than 1 micron at the at least one opening.

6. The apparatus of claim 5 wherein said first and second conductive electrodes are separated by less than 300 nm at the at least one opening.

7. The apparatus of claim 6 wherein said first and second conductive electrodes are separated by less than 200 nm at the at least one opening.

8. The apparatus of claim 7 wherein said first and second conductive electrodes are separated by approximately 50 nm at the at least one opening.

9. The apparatus of claim 1 wherein the at least one opening tapers inwardly from the first surface of said insulating element to the second surface of said insulating element.

10. The apparatus of claim 1 further comprising a substrate disposed between said first and second conductive electrodes for providing structural support.

11. The apparatus of claim 1 wherein the at least one opening has a diameter approximately in the range of 2–3 microns.

12. The apparatus of claim 1 wherein said first and second electrodes are formed of at least one of gold, chrome or titanium.

13. The apparatus of claim 1 wherein said insulating element is formed of silicon nitride or alumina.

14. A method comprising: forming a layer of thin dielectric material on a substrate that has a first specified thickness of a sufficient thickness to maintain structural integrity; forming a first electrode on the first surface of said thin dielectric material, said first electrode being formed of a metal material; forming at least one hole in said substrate; forming a second electrode on a second surface of the substrate including the at least one holes, such that at least a portion of the second electrode is on a second surface of the thin dielectric material; forming holes in the second electrode, thin dielectric material and the first electrode, which holes have side surfaces where the first and second electrodes are separated by a width of the thin dielectric material, wherein said thin dielectric material has a thickness which is less than the mean free path of the gas intended to be ionized; and generating ions to form thrust.

15. The method claim 14 wherein the step of forming electrodes comprises depositing at least one of gold, chrome, or titanium.

16. The method of claim 14 wherein the step of forming a thin dielectric comprises depositing silicon nitride or alumina.

17. The method of claim 14 wherein said thin dielectric has a thickness less than 1 micron.

18. The method of claim 17 wherein said thin dielectric has a thickness less than 500 nm.

19. The method of claim 18 wherein said thin dielectric has a thickness less than 300 nm.

20. The method of claim 19 wherein said thin dielectric has a thickness of approximately 50 nm.
21. The method of claim 17 further comprising the step of applying a voltage less than 15 volts between said first and second electrodes to form a field between said first and second electrodes in the range of tens to hundreds of megavolts per meter.

22. The method of claim 14 wherein said forming holes in said first and second electrode and said thin dielectric material comprises ion-beam milling.

23. The method of claim 14 wherein the holes formed in said first and second electrodes and said thin dielectric material are approximately 2–3 microns in diameter.

24. A method comprising the steps of: providing an ionization device comprising an insulating element having at least one opening, a first conductive electrode extending on a first surface of said insulating element at the at least one opening and a second conductive electrode extending on a second surface of the insulating element at the at least one opening, wherein said insulating element separates said first and second conductive electrodes at said at least one opening by a thickness less than the mean free path of the molecules within the gas being ionized; applying a potential across the first and second electrodes to generate an ionization field to ionize the molecules; and using ions generated by the ionization field to generate thrust.

25. An apparatus for use with an ion thrusting system, the apparatus comprising: ionization means for ionizing gas molecules passing therethrough to form ions and; accelerator means for accelerating the ions to form thrust, wherein the ionization means comprises: an insulating element having at least one opening, a first conductive electrode extending on a first surface of said insulating element at the at least one opening and a second conductive electrode extending on a second surface of the insulating element at the at least one opening, wherein said insulating element separates said first and second conductive electrodes at said at least one opening by a thickness less than the mean free path of the molecules within the gas being ionized.

26. An apparatus comprising:

a thick supporting portion with at least one opening formed in the thick supporting portion;

an insulating element coated on a surface of the thick supporting portion configured to form a hole within each at least one opening in the thick supporting portion;

first and second metal electrodes coated on surfaces of the thick supporting portion extending into the openings in the thick supporting portion, where the insulating element separates the first and second metal electrodes within the holes of the insulating element by a distance less than the mean free path of a material being ionized; and

means for generating thrust.

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